Special Issue

Design of Nanostructured Materials by Atomic Layer Deposition and Its Applications

Message from the Guest Editors

ALD is a thin film deposition technique allowing for sub-nanometer thickness control, as well as excellent uniformity and conformality on demanding substrates. Although ALD is typically used for the synthesis of oxides nanomaterials, it has been shown that nitrides and metals can also be prepared using this technique.

This Special Issue will aim at gathering resources in the area of the design of nanostructured materials using ALD for different applications such as health, environment and renewable energy. Contributions related to advanced materials design, novel materials properties and original characterization techniques will be as well considered.

This Special Issue will deal with: (i) the design of nanostructured materials with controlled morphology, geometry and crystallinity, (ii) the tuning of interfaces for the obtained materials, (iii) the study of the dependence of the physical-chemical properties on the geometric parameter, and (iv) the investigation of new applications.

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